

In the Specification:

Please amend the specification as follows:

On page 5, line 3, please add the following paragraph describing Figure 1A, before the description of Figure 2:

91 Figure 1A is a simplified illustration of another embodiment of an exposure apparatus having features of the present invention;

Please substitute the following paragraph for the paragraph beginning on page 9, line 10:

92 The central body frame 78 also defines a base frame aperture 106 that is sized and shaped to receive a portion of the optical assembly 36 and the optical frame 20. The central body frame 78 also includes three assembly support mounts 108 that are positioned, spaced apart, along the perimeter of the base frame aperture 106. It should be noted that the assembly support mounts 108 are at approximately the same height along the Z axis as the base support mounts 100, 102, 104. As a result of this design, the base isolation system 40 and the optical isolation system 42 are at approximately the same height along the Z axis and approximately the same plane. As provided herein, the center of the base isolation system 40 is preferably between approximately zero inches and twelve inches of the center of the optical isolation system 42 along the Z axis. Further, as a result of this design, the optical assembly 36 is "nested," i.e. positioned within the base assembly 38 and the optical device 22 can be accessed relatively easily for service and adjustment. Moreover, this minimizes the distance between the assembly support mounts 108 and the base support mounts 100, 102, 104. As a result thereof, distortion and vibration of the central body frame 78 are minimized. As illustrated in Figure 11, the assembly support mounts 108 can be removably secured to the central body frame 78 to facilitate assembly of the exposure apparatus 10 (not illustrated in Figure 11).

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Please add the following paragraph before the paragraph beginning on page 9, line

93 Figure 1A is a simplified illustration of another embodiment of an exposure apparatus 10 having features of the present invention. This embodiment contains the same elements as the embodiment of the exposure apparatus 10 illustrated in Figure 1. For example, this embodiment includes the base assembly 38 that is isolated from the support frame 12 with the base isolation system 40 and the optical assembly 36 that is isolated from the base assembly 38 with the optical isolation system 42. However, in the embodiment illustrated in Figure 1A, the base frame 14 and the support frame 12 are designed so that the base isolation system 40 is positioned at exactly the same height as the optical isolation system 42.

line 1:

Please substitute the following paragraph for the paragraph beginning on page 17,

94 The optical assembly 36 can include (i) the optical frame 20, (ii) the optical device 22, (iii) a sensor column 180, (iv) a portion of the measurement system 24, (v) the first stage base 130, and (vi) the fine stage 132. As a result of the design provided herein, the optical assembly 36 can be easily removed from the exposure apparatus 10. For example, the optical assembly 36 allows the optical device 22 and the optical frame 20 to be removed from the exposure apparatus 10 as a module. Alternately, for example, the optical assembly 36 can be designed without the first stage base 130 and the fine stage 132.

line 3:

Please substitute the following paragraph for the paragraph beginning on page 19,

95 As shown in the Figures, the optical frame 20 supports the first stage base 130 and the fine stage 132. More specifically, the first stage base 130 is secured to the spaced apart upper stage mounts 192. With this design, the optical assembly 36 can be removed from the exposure apparatus 10 after removing the first stage base 130, the fine stage

132, and the rest of the first stage assembly 16. This simplifies the assembly and the disassembly of the exposure apparatus 10. Alternately, in another embodiment, the exposure apparatus can be designed so the optical frame 20 does not support the first stage base 130 and the fine stage 132.

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